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STATEMENT BY APPLICANT**
(Not for submission under 37 CFR 1.99)

Application Number	10588981
Filing Date	2006-08-10
First Named Inventor	RODERICK BOSWELL
Art Unit	2821
Examiner Name	NOT YET ASSIGNED
Attorney Docket Number	F146

U.S.PATENTS

Examiner Initial*	Cite No	Patent Number	Kind Code ¹	Issue Date	Name of Patentee or Applicant of cited Document	Pages, Columns, Lines where Relevant Passages or Relevant Figures Appear
/M.S./	1	4859908		1989-08-22	YOSHIDA ET AL.	
	2	5108535		1992-04-28	ONO ET AL.	
	3	5945677		1999-08-31	LEUNG ET AL.	
	4	6768120		2004-07-27	LEUNG ET AL.	
	5	6975072		2005-12-13	LEUNG ET AL.	
	6	7084407		2006-08-01	JI ET AL.	
↓	7	7176469		2007-02-13	LEUNG ET AL.	

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U.S.PATENT APPLICATION PUBLICATIONS

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Examiner Initial*	Cite No	Publication Number	Kind Code ¹	Publication Date	Name of Patentee or Applicant of cited Document	Pages, Columns, Lines where Relevant Passages or Relevant Figures Appear
/M.S./	1	20070108395		2007-05-17	HORSKY ET AL.	

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FOREIGN PATENT DOCUMENTS

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/M.S./	1	2008094297	WO		2008-08-07	FEI COMPANY		<input type="checkbox"/>
/M.S./	2	2005038821	WO		2005-04-28	FEI COMPANY		<input type="checkbox"/>
/M.S./	3	2005081940	WO		2005-09-09	FEI COMPANY		<input type="checkbox"/>

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NON-PATENT LITERATURE DOCUMENTS

Examiner Initials*	Cite No	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc), date, pages(s), volume-issue number(s), publisher, city and/or country where published.	T ⁵
/M.S./	1	COATH ET AL., C.D., "A High-Brightness Duoplasmatron Ion Source for Microprobe Secondary-Ion Mass Spectrometry," Rev. Sci. Instrum., American Institute of Physics, February 1995, pgs. 1018-1023, Volume 66(2).	<input type="checkbox"/>
/M.S./	2	HOPWOOD, J., "A Microfabricated Inductively-Coupled Plasma Generator," Journal of Microelectromechanical Systems, September 2000, pgs. 309-313, Volume 9, Issue 3.	<input type="checkbox"/>

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/M.S./	3	JIANG ET AL., X., "Mini RF-Driven Ion Sources for Focused Ion Beam Systems," Review of Scientific Instruments, American Institute of Physics, April 2003, pgs. 2288-2292, Volume 74, No. 4.	<input type="checkbox"/>
/M.S./	4	JOHNSON, W., "Electrostatically-Shielded Inductively-Coupled RF Plasma Sources," High Density Plasma Sources, 1995, pgs. 100-148, Chapter 3.	<input type="checkbox"/>
/M.S./	5	SMITH ET AL., N.S., "High Brightness Inductively Coupled Plasma Source for High Current Focused Ion Beam Applications," J. Vac. Sci. Technol., American Vacuum Society, Nov/Dec. 2006, pgs. 2902-2906, Volume B. 24(6).	<input type="checkbox"/>
/M.S./	6	YIN ET AL., Y., "Miniatrization of Inductively Coupled Plasma Sources," Plasma Science, October 1999, pgs. 1516-1524, Volume 27, Issue 5.	<input type="checkbox"/>

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